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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

Yukihiko SHIRAKAWA

: GROUP ART UNIT: 2879

SERIAL NO.: 09/866,732

TECHNOLOGY CENTER 2800 #14B Just
M. Brunson
7/17/03

FILED: May 30, 2001

: EXAMINER: HARPER, H.

FOR: THIN-FILM EL DEVICE, AND ITS FABRICATION PROCESS

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

In response to the Office Action dated March 31, 2003, please reconsider the application in view of the following amendment and remarks.

IN THE CLAIMS

Please add the following new Claims.

- 6. (New) The thin-film EL device according to Claim 1, wherein said electrically insulating substrate maintains a given heat-resistant strength without contaminating said patterned electrode layer and said dielectric layer.
- 7. (New) The thin-film EL device according to Claim 1, wherein said electrically insulating substrate is selected from the group consisting of alumina (Al₂O₃), quartz glass (SiO₂), magnesia (MgO), forsterite (2MgO•SiO₂), steatite (MgO•SiO₂), mullite (3Al₂O₃•2SiO₂), beryllia (BeO), zirconia (ZrO₂), aluminum nitride (AlN), silicon nitride (SiN), silicon carbide (SiC), crystallized glass, high heat-resistance glass, green sheet glass substrates and enameled metal substrates.

